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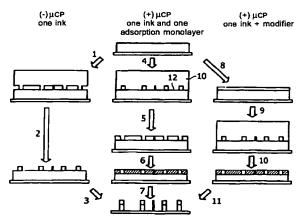
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(54) Title: A METHOD OF FORMING A PATTERNED LAYER ON A SUBSTRATE



(57) Abstract: A method of forming a patterned self-assembled monolayer (20) on a substrate (24) by means of a soft lithographic patterning process, the method comprising: a) providing patterning means (10) for defining the required pattern of said patterned self-assembled monolayer (20); b) forming a self-assembled monolayer (20) on a surface (22) of said substrate (24); c) applying said patterning means (10) to said surface of said substrate (24), said patterning means (10) being arranged to deliver a modifier to selected areas of said substrate surface, said selected areas corresponding to said required pattern or a negative thereof, said modifier comprising a chemical and being arranged to alter at said selected areas the strength of interaction between the molecules of said self-assembled monolayer (10) and said surface of said substrate (24); and d) selectively removing or replacing areas of said self-assembled monolayer (20) that, after step c), exhibit a lower strength of interaction between the molecules thereof and said surface of said substrate, thereby to form a self-assembled monolayer (20) having said required pattern. The modifier may be selected to decrease or increase the strength of interaction between the molecules of the substrate, as required by the process.



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